



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: $>90\%CA$
3. SURFACE QUALITY(S1,S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633\text{nm}$ (SUBSTRATE)
5. PARALLELISM(S1,S2): $<3\text{ arcmin}$
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}}>90\%$, $T_{\text{abs}}>85\%@380-475\text{ nm}, 45^\circ\text{ AOI}$
 $R_{\text{avg}}>95\%$, $R_{\text{abs}}>90\%@505-800\text{ nm}, 45^\circ\text{ AOI}$
 AR COATING(S2): $R_{\text{abs}}<2\%@380-475\text{ nm}, 45^\circ\text{ AOI}$

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|--|--------|--------------|---|--------|-------|-----|
| DRAWING PROJECTION | | | LBTEK | | | |
| | NAME | DATE | | | | |
| DRAWN | LZHOU | JUL./30th/24 | SHORTWAVE DICHOIC MIRROR $\phi 12.7\text{ mm} \times 3.2\text{ mm}, 490\text{ nm}$ | | | |
| APPROVAL | WCHENG | JUL./30th/24 | MATERIAL | WEIGHT | SCALE | REV |
| FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES | | | UVFS | 0.9 g | 2:1 | A |